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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO. CONFIRMATION NO.	
10/543,092	07/22/2005	Takashi Miyamatsu	70020.0066USWO 4088	
23552 MERCHANT	7590 06/26/2007 & GOLUD PC		EXAMINER	
P.O. BOX 2903 MINNEAPOLIS, MN 55402-0903			CHU, JOHN S Y	
MINNEAPOL	18, MIN 33402-0903		ART UNIT PAPER NUMBER	
			1752	
			MAIL DATE	DELIVERY MODE
			06/26/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

		Application No.	Applicant(s)
		10/543,092	MIYAMATSU ET AL.
	Office Action Summary	Examiner	Art Unit
		John S. Chu	1752
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the o	correspondence address
A SH WHIC - Exter after - If NC - Failu Any r	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DANS IN THE MAIL	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tir vill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. mely filed the mailing date of this communication. TO (35 U.S.C. § 133)
Status	· · · · · · · · · · · · · · · · · · ·	•	
	Responsive to communication(s) filed on 22 Ju This action is FINAL . 2b) This Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro	
Dispositi	on of Claims		
5)□ 6)⊠ 7)□ 8)□ Applicati 9)□ 10)□	Claim(s) 1-8 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) 1-8 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or are subject to restriction and/or are specification is objected to by the Examine The drawing(s) filed on is/are: a) access Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Examine Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Examine The oath or declaration is objected to by the Examine Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Examine The oath	r election requirement. r. epted or b) □ objected to by the drawing(s) be held in abeyance. Section is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).
Priority u	ınder 35 U.S.C. § 119		·
a)[Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau See the attached detailed Office action for a list of	s have been received. s have been received in Applicati ity documents have been receive (PCT Rule 17.2(a)).	on No ed in this National Stage
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Attachment	t(s)		
1) Notice 2) Notice 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date <u>7/22/05, 6/13/07</u> .	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate

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DETAILED ACTION

This Office action is in response to the application filed July 22, 2005.

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

2. Claims 1-8 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by EBATA et al (6,908,722).

The claimed invention is drawn to the following:

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1. A sulfonium salt compound shown by the following formula (1),

$$(R^1)_p$$

$$(R^2)_q S^+ X^- \qquad (I)$$

wherein R¹ represents a linear or branched alkyl group having 1-14 carbon atoms, a monovalent hydrocarbon group having an alicyclic skeleton and containing 3-14 carbon atoms, a linear or branched alkoxyl group having 1-14 carbon atoms, a group represented by -OR³ (wherein R³ is a monovalent hydrocarbon group having an alicyclic skeleton and containing 3-14 carbon atoms), a linear or branched alkyl sulfanyl group having 1-14 carbon atoms, an organic sulfanyl group having an alicyclic skeleton and containing 3-14 carbon atoms, a linear or branched alkane sulfonyl group having 1-14 carbon atoms, or an organic sulfonyl group having an alicyclic skeleton and containing 3-14 carbon atoms, two or more R¹ being either the same or different, R² represents a substituted or unsubstituted, linear, branched, or cyclic alkyl group having 1-14 carbon atoms, or two or more R² groups bond to form a monocyclic structure having 3-14 carbon atoms or a polycyclic structure having 6-14 carbon atoms, two or more R² groups being either the same or different, p is an integer of 0-7, q is an integer of 0-6, n is an integer of 0-3, and X represents a sulfonic acid anion.

EBATA et al anticipates the claimed invention in <u>Table 7</u>, <u>Comparative Example 2</u> wherein the photoacid generator is (a-4) defined in <u>column 74</u>, <u>lines 43-44</u> for a 1-(4-n-butoxynaphthaleny-1-yl)tetrahydrothiophenium nonafluoro-n-butanesulfonate. This compound anticipates the claimed sulfonium salt as recited in claim 1. In <u>Table 7</u>, <u>column 78</u>, <u>lines 20-25</u> the photoresist components are disclosed that are used with the sulfonium salt acid generator.

No claims are allowed.

3. Claims 1 and 3-8 are rejected under 35 U.S.C. 102(b) as being clearly anticipated by SUWA et al (6,908,722).

SUWA et al anticipates the invention at Examples 1-8 and 11-13 wherein one of the following are disclosed:

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Acid Qenerators(A):

- (A-1) 4-Hydroxy-1-naphthyltetrahydrothiophenium trifluoromethanesulfonate
- (A-2) 4-Methoxy-1-naphthyltetrahydrothiophenium trifluoromethanesulfonate
- (A-3) 4-n-Butoxy-1-naphthyltetrahydrothiophenium trifluoromethanesulfonate
- (A-4) 4-t-Butoxy-1-naphthyltetrahydrothiophenium trifluoromethanesulfonate
- (A-5) 4-n-Butoxy-1-naphthyltetrahydrothiophenium n-nonafluorobutanesulfonate

No claims are allowed.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 1-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over EBATA et al (6,908,722) or SUWA et al (6,908,722).

The claimed invention has been recited above and included by reference.

EBATA et al has been recited above for the use of a 1-(4-n-butoxynaphthaleny-1-yl)tetrahydrothiophenium nonafluoro-n-butanesulfonate in Comparative Example 2 in a photoresist composition.

The reference lacks the use of the other sulfonium salts as disclosed in column 17, lines 10-40 wherein heterocyclic sulfonium salts attached to a naphthalene is disclosed. However the listing of the sulfonium compounds are a teaching guide to the skilled artisan that other

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sulfonium salts as listed are suitable for the photoresist composition such that reasonably the same or similar results can be expected if used in a working example.

SUWA et al has been discussed above, however lacks the use of a nonafluorobutanesulfonate anion in a working example as disclosed in column 7, lines 30-42.

It would have been *prima facie* obvious to one of ordinary skill in the art of photoresist composition to use any of the listed sulfonium salts, (i-55) – (i-57) as disclosed in column 17 in a working photoresist composition and reasonably expect same or similar results as recited in EBATA et al for high transparency to deep ultraviolet rays and producing acids with high acidity.

It would have been *prima facie* obvious to one of ordinary skill in the art of photoresist compositions to use any of the listed anions of column 7, line s30-37 of SUWA et al in the working examples of SUWA et al and reasonably expect same or similar results for high resolution.

- 6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. KODAMA (2005/0287473) and (2005/0266336) disclose sulfonium salts, which meet the claimed invention, however are not prior art in view of the filing dates.
- 7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday Friday from 9:30 am to 6:00 pm.

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

The fax phone number for the USPTO is (571) 273-8300.

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/John S. Chu/

Primary Examiner, Group 1700

J.Chu June 21, 2007